

Appl. No. 10/632,752

Amdt. dated 4/22/05

Reply to Office action of March 29, 2005

SPECIFICATION AMENDMENTS

Please replace the paragraph between page 9, line 19 and page 10, line 4 with the following:

With the objects of the invention in view, there is also provided a reflective optical mirror for the lithographic exposure of semiconductor products. The mirror comprises a substrate, a multilayer structure disposed above the substrate for reflecting electromagnetic radiation through constructive interference, and a capping layer disposed above the multilayer structure. The capping layer is formed of a material on which a natural oxide layer forms in air. The material of the capping layer is doped with ~~a doping~~ and the oxide layer includes a region having a layer thickness with the same doping as the doping of the capping layer being incorporated into an oxide of the oxide layer.